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Sommario/riassunto

Patterning or lithography is at the core of modern science and technology and cuts across all disciplines. With the emergence of nanotechnology, conventional methods based on electron beam lithography and extreme ultraviolet photolithography have become prohibitively expensive. As a result, a number of simple and unconventional methods have been introduced, beginning first with research demonstrations in the mid 1990s. This book focuses on these unconventional patterning techniques and their applications to optics, organic devices, electronic devices, biological devices, and fluidics.